

INFORMATION DISCLOSURE STATEMENT

Applicant : Hojo et al.
App. No : 10/554,380
Filed : September 29, 2006
For : POSITIVE PHOTORESIST
COMPOSITION AND METHOD FOR
FORMING RESIST PATTERN
Examiner : Anca Eoff
Art Unit : 1795

CERTIFICATE OF EFS WEB
TRANSMISSION

I hereby certify that this correspondence, and any other attachment noted on the automated Acknowledgement Receipt, is being transmitted from within the Pacific Time zone to the Commissioner for Patents via the EFS Web server on:

September 5, 2008

(Date)


Neil S. Bartfeld, Ph.D., Reg. No. 39,901

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 5 (five) references. Please place these documents in the application file.

No fees are believed to be due. However, the Commissioner is hereby authorized to charge any additional fees which may be required to Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 9/5/08By: 

Neil S. Bartfeld, Ph.D.
Registration No. 39,901
Agent of Record
Customer No. 20,995
(619) 235-8550